

L Number	Hits	Search Text	DB	Time stamp
1	49	("6278124" "4351892" "4544847" "4868395" "4985634" "6344116" "5824437" "5952155" "4377767" "4572956" "5025168" "4385434" "4514638" "5789119" "6011268" "6034376" "4468565" "4525629" "4887282" "5608773" "5627871" "5784150" "6051346" "6225025" "6225025" "4475223" "4902930" "4914304" "5268951" "5377009" "5807648" "5866913" "6040095" "4438336" "4445040" "4532426" "4546260" "4569068" "4590382" "4825087" "4988284" "5582939" "5759724" "5811211" "5831274" "5834783" "5892231" "5935735" "5973332" "6090528").pn.	USPAT	2003/06/25 14:02

Most Frequently Occurring Classifications of Patents Returned
From A Search of 09993500 on March 29, 2002

Original Classifications

8 430/5
7 250/492.2
5 378/34
5 430/296
4 250/398
3 250/491.1
3 250/492.22
2 250/396ML
2 250/492.23
2 430/30

Cross-Reference Classifications

5 250/398
5 250/492.2
5 430/296
4 250/491.1
4 430/30
2 250/396ML
2 250/396R
2 250/492.3
2 250/505.1
2 378/208
2 430/311
2 430/322
2 430/5
2 438/975

Combined Classifications

12 250/492.2
10 430/296
10 430/5
9 250/398
7 250/491.1
6 378/34
6 430/30
4 250/396ML
4 250/492.22
3 250/492.23
2 250/396R
2 250/492.3
2 250/505.1

2 355/53
2 356/401
2 378/208
2 430/311
2 430/322
2 438/975

Titles of Most Frequently Occurring Classifications of Patents Returned
From A Search of 09993500 on March 29, 2002

12 250/492.2 (7 OR, 5 XR)

Class 250 : RADIANT ENERGY

250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

250/492.2 .Irradiation of semiconductor devices

10 430/296 (5 OR, 5 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING

NONPLANAR OR

PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT

430/296 .Electron beam imaging

10 430/5 (8 OR, 2 XR)

Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF

430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF
MAKING

430/5 .Radiation mask

9 250/398 (4 OR, 5 XR)

Class 250 : RADIANT ENERGY

250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING

250/398 .With target means

7 250/491.1 (3 OR, 4 XR)

Class 250 : RADIANT ENERGY

250/491.1 MEANS TO ALIGN OR POSITION AN OBJECT RELATIVE
TO A SOURCE OR DETECTOR

6 378/34 (5 OR, 1 XR)

Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES

378/1 SPECIFIC APPLICATION

378/34 .Lithography

- 6 430/30 (2 OR, 4 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST
OR MEASUREMENT
- 4 250/396ML (2 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
250/396ML .Magnetic lens
- 4 250/492.22 (3 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.22 ..Pattern control
- 3 250/492.23 (2 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.23 ..Variable beam
- 2 250/396R (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR
FOCUSSING
- 2 250/492.3 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation
- 2 250/505.1 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/505.1 RADIATION CONTROLLING MEANS
- 2 355/53 (1 OR, 1 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/53 .Step and repeat
- 2 356/401 (1 OR, 1 XR)
Class 356 : OPTICS: MEASURING AND TESTING

356/399 BY ALIGNMENT IN LATERAL DIRECTION
356/401 .With registration indicia (e.g., scale)

2 378/208 (0 OR, 2 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/204 ACCESSORY
378/208 .Object holder or support

2 430/311 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING
NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/311 .Making electrical device

2 430/322 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
RADIATION SENSITIVE MATERIAL, OR PRODUCING
NONPLANAR OR
PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/322 .Forming nonplanar surface

2 438/975 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/975 SUBSTRATE OR MASK ALIGNING FEATURE
LUS Search Results for S/N 09993500, Searched March 29, 2002

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5973332
6090528